

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2003-016857

(43)Date of publication of application : 17.01.2003

(51)Int. Cl. H01B 13/00  
C23C 14/58  
H01L 21/3205  
H01L 31/04

(21)Application number : 2001-196560

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(22)Date of filing : 28.06.2001

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## (54) METHOD FOR REDUCING RESISTANCE OF TRANSPARENT CONDUCTIVE FILM FORMED ON BASE MATERIAL

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a method for reducing resistance of a transparent conductive film at a low temperature using a simple process, in particular, a method for reducing the resistance of the transparent conductive film formed on a plastic base material.

**SOLUTION:** This method for reducing the resistance of the oxide transparent conductive film formed on the base material has a treatment process for applying ultraviolet rays to the oxide transparent conductive film formed on the base material in vacuum or reducing gas atmosphere, while keeping the conductive film at a temperature of 25-300° C.

